



PATENT
Atty. Dkt. AMAT/8284/CMP/W-C/RKK

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Verhaverbeke

Serial No.: 10/676,182

Confirmation No.: Unknown

Filed: September 30, 2003

For: Dilute Sulfuric Peroxide at
Point-of-Use

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§ Group Art Unit: Unknown

§ Examiner: Unknown

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MAIL STOP DD
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on December 30, 2003 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.	
<u>12/30/03</u>	<u>Denny Mays</u>
Date	Signature

Dear Sir:

INFORMATION DISCLOSURE STATEMENT

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No. 20-0782/APPM/8284/BTP.

Respectfully submitted,



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U.S. Department of Commerce, Patent and Trademark Office					Docket No.	Serial No.		
(PTO Form 1449 modified) JAN 02 2004					AMAT/8284/CMP/W-C/RKK	10/676,182		
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT					Applicant Verhaverbeke	Confirmation No.: Unknown		
(Use several sheets if necessary)					Filing Date	Group		
	Examiner	Unknown			September 30, 2003	Unknown		
U.S. Patent Documents								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
	A1	5,326,490	07/05/94	Mori, et al.	252	79.2	11/15/91	
	A2	5,294,570	03/15/94	Fleming, Jr., et al.	437	239	01/29/92	
	A3	5,052,421	10/01/91	McMillen	134	2	07/27/90	
	A4	4,220,706	09/02/80	Spak	430	318	05/10/78	
	A5							
	A6							
	A7							
	A8							
	A9							
Foreign Patent Documents								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1	02/10480	02/07/02	WO	C23G	1/00	<input type="checkbox"/>	<input type="checkbox"/>
	B2	01/24244	04/05/01	WO	H01L	21/311	<input type="checkbox"/>	<input type="checkbox"/>
	B3	0 918 081 A1	05/26/99	EP	C09K	13/08	<input type="checkbox"/>	<input type="checkbox"/>
	B4	0 477 504 A1	04/01/92	EP	H01L	21/306	<input type="checkbox"/>	<input type="checkbox"/>
	B5	7183287	07/21/95	JP	H01L	21/308	<input type="checkbox"/>	<input type="checkbox"/>
OTHER ART								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
	C1	Archer, et al. "Real Fab Comparisons Reveal Advantage to Inorganic-based Polymer Removal," Solid State Technology – Semiconductor Manufacturing and Wafer Fabrication, December 2002						
	C2	Archer, et al. "Removing Postash Polymer Residue from BEOL Structures Using Inorganic Chemicals," Micro, June 2001						
	C3	Verhaverbeke, et al., Improved Rinsing Efficiency After SPM (H_2SO_4/H_2O_2) by Adding HF, Proceedings of the Second International Symposium on Ultra-Clean Processing of Silicon Surfaces (1994)						
	C4	Khan, "Use of Lithographically Defined Metal Masks in Selective Chemical Etching of Patterns in Thin Films: Microelectronic Applications," Thin Solid Films, 206 (1991) 269-274						
Examiner					Date Considered			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								